

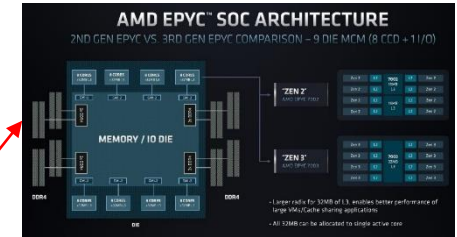
# 연구실 소개



반도체설계자동화연구실  
(Semiconductor Design Automation Lab.)

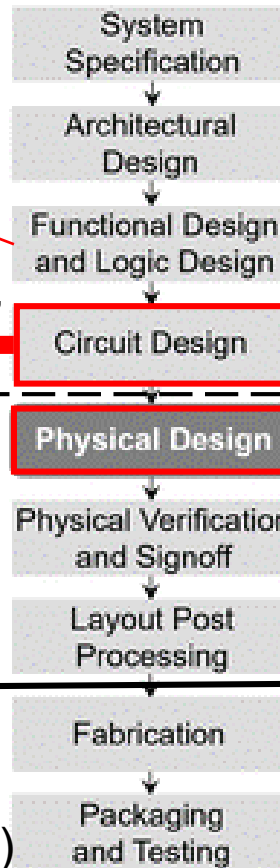
지도교수: 박희천

- 시스템반도체 설계 자동화 & 최적화
  - VLSI (초고밀도 집적회로) & SoC (단일 칩 시스템)
  - EDA (전자설계자동화), CAD (컴퓨터이용설계)



▲ System architecture

## ▼ VLSI EDA flow



## ▼ RTL (Register-transistor level)

```

input clk, rst;
input [63:0] A, B, C, D, E, F;
input Cin;
output reg [63:0] S;
output reg Cout;

reg [63:0] S1, S2, S3, S4;
reg Cout1, Cout2, Cout3, Cout4;

always @(posedge clk or posedge rst) begin
    if (rst) begin
        S <= 63'b0;
        S1 <= 63'b0;
    end
end
    
```

## Logic Synthesis

## Standard cells

```

n66247) );
XOR2xp5_ASAP7_75t_R_U65005 ( .A(n30906), .B(n70177), .Y(n70177) );
XNOR2xp5_ASAP7_75t_R_U65006 ( .A(n31174), .B(n70945), .Y(n70945) );
AOI22xp5_ASAP7_75t_R_U65007 ( .A1(n62051), .A2(n62050), .B1(n62048), .Y(n62052) );
OAI21xp5_ASAP7_75t_R_U65008 ( .A1(n67276), .A2(n67275), .B1(n67277) );
XNOR2xp5_ASAP7_75t_R_U65009 ( .A(n31416), .B(n71224), .Y(n71224) );
AOI31xp33_ASAP7_75t_R_U65010 ( .A1(n67015), .A2(n67014), .B1(n67012), .Y(n67016) );
OAI22xp5_ASAP7_75t_R_U65011 ( .A1(n60266), .A2(n60265), .B1(n60263), .Y(n60267) );
    
```

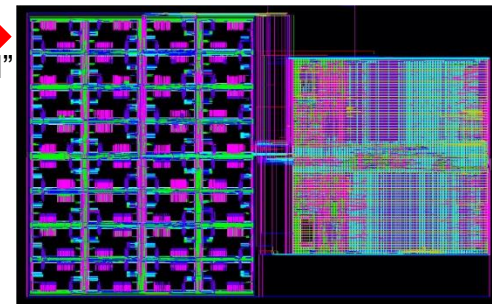
▲ Gate-level netlist

```

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```

## ▼ Gate-level netlist

## Place & Route (P&R)



▲ GDS (Graphic design system)

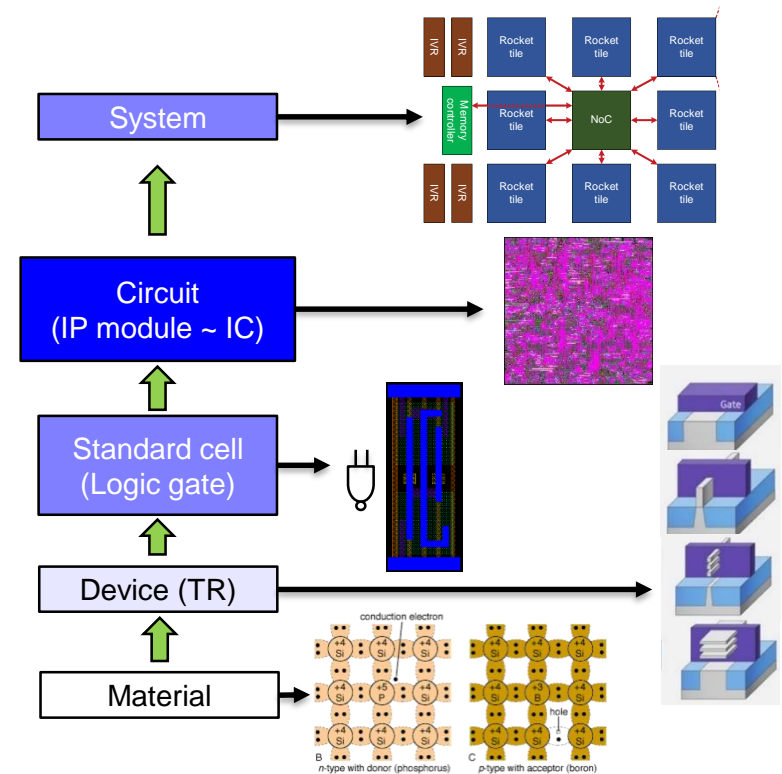
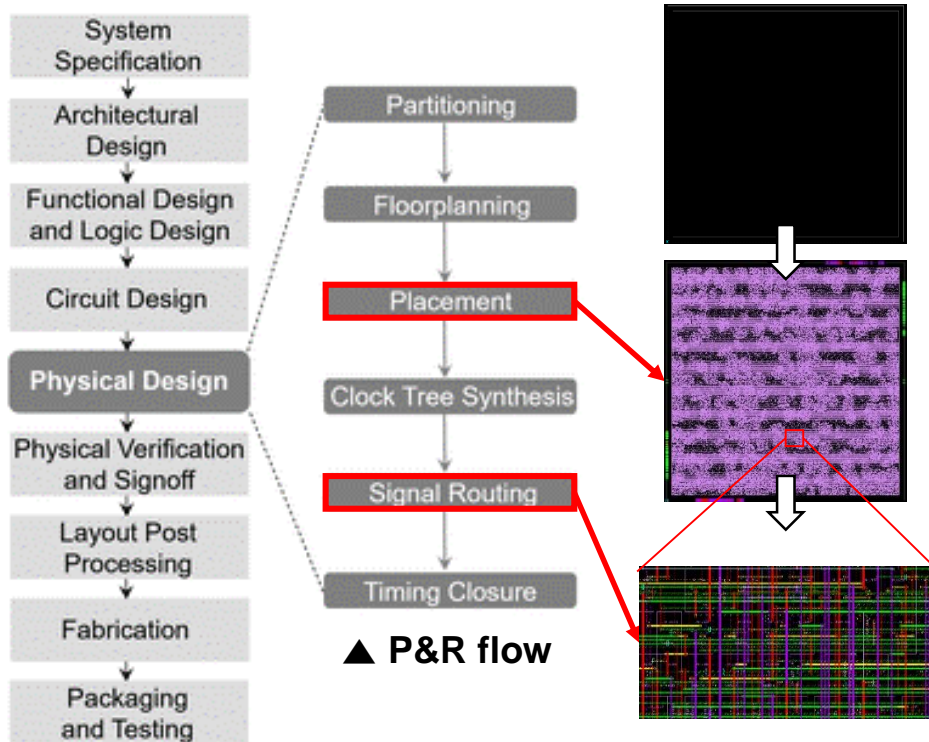
설계

생산  
(공정)

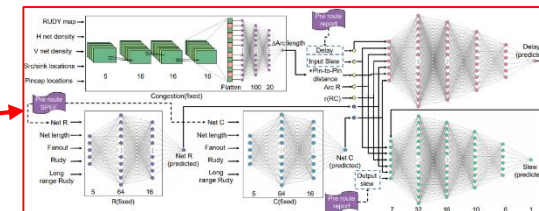
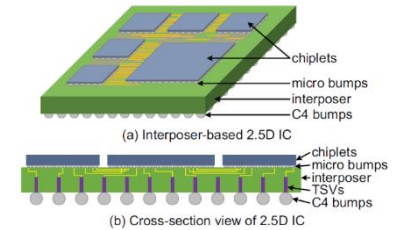


◀ Wafer

- Place & Route 알고리즘 개선 및 개발
- 설계 자동화&최적화 대상: Standard cell ~ IC ~ System



# Machine learning for EDA



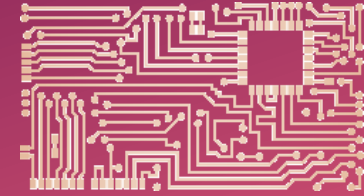
- ~23.2: EDA flow 및 design stage 학습
- 23.3 ~ 23.6: EDA tool 사용
- 23.7 ~ (?): 세부 주제 학습 및 연구
  - 수직적층 구조 → EDA for 3D/2.5D design
  - 최신 공정 & design rules → design-rule-aware EDA
  - Memory → PIM 구조 → EDA for PIM architecture
  - CPU architecture → neuromorphic → physical design (EDA) for NPU
  - ML → Early-stage design prediction & optimization
  - ML & RL → RL-based design automation
  - .....

	synopsys®	cā d e n c e®
Synthesis	Design Compiler	Genus
Place & Route	IC Compiler	Innovus
Signoff Analysis	PrimeTime, PrimeRail, ...	Tempus, Voltus, ...

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# Thank you!

